

09/730,672

In response to the Office Action, please amend the above-identified application as follows:

IN THE CLAIMS:

Please amend claims 1 and 2, as follows:

1 1. (Amended) A method for lighting an inductive plasma in a
2 plasma processing apparatus having a matching network, the
3 method comprising the steps of:
4 determining a matching condition under which the
5 matching network is tuned to a first plasma as a capacitive
6 plasma;
7 presetting the matching network at the matching
8 condition determined in said determining step;
9 lighting a second plasma in accordance with the preset
10 matching condition and at a desired power, where the desired
11 power includes a power required to maintain the second plasma
12 as a capacitive plasma and an excess power; and
13 allowing an inductive plasma to light due to the excess
14 power.

1 2. (Amended) A method according to claim 1, wherein said
2 determining step further comprises:
3 lighting the first plasma;
4 setting a power delivered to the first plasma at not
5 more than about 20 watts;
6 allowing the matching network to tune to the first
7 plasma as a capacitive plasma; and
8 recording the matching condition under which the
9 matching network is tuned to the first plasma.